PLASMA PROCESSING APPARATUS

Abstract

A plasma processing apparatus comprises a plasma processing chamber, a substrate support, an electrode or an antenna, a high frequency power supply, a consuming member, an electricity storage unit and a power receiving coil. The electrode or an antenna is disposed such that a space within the plasma processing chamber is located between the electrode or the antenna and the substrate support. The high frequency power supply is configured to generate high frequency power and is electrically connected to the substrate support, the electrode or the antenna. The power consuming member is disposed within the plasma processing chamber or the substrate support. The electricity storage unit is electrically connected to the power consuming member. The power receiving coil is electrically connected to the electricity storage unit and capable of receiving power from a power transmitting coil by electromagnetic induction coupling.

Fig. 3